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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/945,554	08/30/2001	Leonard Forbes	1303.028US1	1837
21186	7590 03/12/2004		EXAMINER	
SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.			DICKEY, THOMAS L	
P.O. BOX 293	-		ART UNIT	PAPER NUMBER
MINNEAPOLIS, MN 55402			2826	
			DATE MAILED: 03/12/2004	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s) FORBES, LEONARD				
•		09/945,554					
	Office Action Summary	Examiner	Art Unit				
		Thomas L Dickey	2826	pw			
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover sheet with the c	orrespondence addre	ess			
THE - Exte after - If the - If NC - Failt Any	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. nsions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. e period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be timer within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed rs will be considered timely. the mailing date of this commodities (35 U.S.C. § 133).	nunication.			
Status							
1)⊠	Responsive to communication(s) filed on 26 Ja	nuary 2004.					
2a)⊠	This action is FINAL. 2b) This	action is non-final.					
3)□	Since this application is in condition for allowar	application is in condition for allowance except for formal matters, prosecution as to the merits is					
	closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	53 O.G. 213.				
Disposit	ion of Claims						
5)⊠ 6)⊠ 7)⊠	Claim(s) 1,2,4-12,19-27,29-32,34-38,40-44 and 46-50 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. Claim(s) 7-12,19-27,29-32,34-38,40-44 and 46-49 is/are allowed. Claim(s) 1 and 2 is/are rejected. Claim(s) 4-6 and 50 is/are objected to. Claim(s) are subject to restriction and/or election requirement.						
Applicati	ion Papers						
9)□	The specification is objected to by the Examine	r.					
	The drawing(s) filed on 30 August 2001 and 26		oted or b) objected	to by the			
Examine	:			-			
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
11)□	Replacement drawing sheet(s) including the correction. The oath or declaration is objected to by the Ex-	-		• •			
Priority u	ınder 35 U.S.C. § 119						
a)l	Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau see the attached detailed Office action for a list of	have been received. have been received in Application ity documents have been received (PCT Rule 17.2(a)).	on No ed in this National Sta	age			
Attachmen	t(s)						
2) ☐ Notic 3) ⊠ Inforr	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date 1/26/04.	4) Interview Summary (Paper No(s)/Mail Da 5) Notice of Informal Pa	ite	2)			

DETAILED ACTION

1. The amendment filed on 01/26/04 has been entered.

Drawings

2. The proposed substitute sheets of drawings, filed on 01/26/04 have been approved.

Claim Rejections - 35 USC § 103

- **3.** The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1 and 2 are rejected under 35 U.S.C. 103(a) as being unpatentable over FORBES ET AL. (6,141,248) in view of GARDNER ET AL. (US 6169306 B1).

Forbes et al. discloses a memory cell with a pair of cross coupled inverters 206-308 and 210-312, wherein each inverter includes an NMOS transistor 308,312 and a PMOS transistor 206,210, and wherein at least one of the NMOS transistors 308,312 includes: a first source/drain region 118 and a second source/drain region 122 separated by a channel region 120a in a substrate 120; a floating gate 116 opposing the channel region 120a and separated therefrom by a gate oxide 126; and a control gate 114 opposing the floating gate 116, wherein the control gate 114 is separated from the floating gate 116

Art Unit: 2826

by a intergate insulator 124. With regard to claim 2 Forbes et al. discloses a pair of bitlines coupled to the pair of cross coupled NMOS floating gate transistors at a pair of voltage nodes through a pair of access transistors so that the floating gates are adapted to be programmed with a respective charge state such that the SRAM cell has a definitive asymmetry. Note figures 5B and 8A and column 5 lines 1-60 of Forbes et al. Forbes et al. does not disclose that the intergate insulator is a low tunnel barrier intergate insulator including a metal oxide insulator selected from the group consisting of PbO or Al₂O₃.

However Gardner et al. discloses a memory cell including at least one NMOS transistor wherein the NMOS transistor includes an intergate insulator 18 comprising any of a fairly large group of transition metal oxide insulators including Al₂O₃, which is a member of the group consisting of PbO or Al₂O₃. Note figure 1 and column 3 lines 24-59 of Gardner et al. Note that Gardner et al.'s intergate insulator may be formed by sputtering at low temperatures. Applicant reports that an inherent property of low-temperature sputtered Ta₂O₅, Perovskite oxide, and Al₂O₃ intergate insulators is that they have low tunnel barriers. Note application, pages 26-30 and 32. Therefore, it would have been obvious to a person having skill in the art to replace the intergate insulator of Forbes et al.'s memory cell with the transition metal oxide Ta₂O₅, Perovskite oxide BST, or Al₂O₃ low tunnel barrier intergate insulator such as taught by Gardner et al. (note that Gardner et al. does not consider the low tunnel barrier property important enough to mention, it is simply inherent) in order to increase the control gate capacitance without

Page 4

Art Unit: 2826

requiring that the intergate insulator be thinned to the point where breakdown becomes a hazard. Note that column 2 lines 7-57 of Gardner et al. 6,210,999 teaches the motivation of using Al₂O₃ as an intergate insulator in order to increase the control gate capacitance without requiring that the intergate insulator be thinned to the point where breakdown becomes a hazard.

Allowable Subject Matter

4. Claims 7-12,19-21, 22-27, 29-32, 34-38, and 40-42 are allowed over the references of record because none of these references disclosed or can be combined to yield the claimed invention such as a memory cell comprising at least a pair of cross coupled NMOS transistors, wherein at least one of the NMOS includes a first source/drain region and a second source/drain region separated by a channel region in a substrate; a floating gate opposing the channel region and separated therefrom by a gate oxide; and a control gate opposing the floating gate, wherein the control gate is separated from the floating gate by a low tunnel barrier intergate insulator, and wherein a metal layer is formed on the floating gate in contact with a low tunnel barrier intergate insulator as recited in claims 7,11,22, 26,31, and 37, or wherein the control gate is the gate having a metal layer formed thereon in contact with a low tunnel barrier intergate insulator as recited in claims 8,23,27,32 or wherein the low tunnel barrier intergate insulator includes a metal layer in contact with one of the floating gate and the control gate, as recited in

Art Unit: 2826

claims 9,19,24, and 29, or the necessary methods of forming the devices of claims 22 and 23, said necessary methods being recited in claims 41 and 42.

- 5. Claims 43,44, and 46-49 are allowed over the references of record because none of these references disclosed or can be combined to yield the claimed invention such as a method for operating an SRAM cell which includes a pair of cross coupled floating gate transistors, comprising writing to at least one of the cross coupled floating gates of the SRAM cell using channel hot electron injection, wherein the cross coupled floating gate transistors each include: a first source/drain region and a second source/drain region separated by a channel region in a substrate; a floating gate opposing the channel region and separated therefrom by a gate oxide; and a control gate opposing the floating gate, wherein the control gate is separated from the floating gate by a low tunnel barrier intergate insulator; erasing charge from the floating gate by tunneling electrons off of the floating gate and onto the control gate; sensing a logic state of the SRAM cell in a start up mode, and writing to the floating gate by tunneling electrons from the control gate to the floating gate, as recited in claim 43.
- **6.** Claims 4-6 and 50 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Application/Control Number: 09/945,554 Page 6

Art Unit: 2826

Response to Arguments

7. Applicant's arguments with respect to claims 1 and 2 have been considered but are most in view of the new ground(s) of rejection.

Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, THIS ACTION IS MADE FINAL. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thomas L Dickey whose telephone number is (571)

Application/Control Number: 09/945,554

Art Unit: 2826

272-1913. The examiner can normally be reached on Monday through Thursday 8 AM

to 6 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Nathan Flynn can be reached on (703) 308-6601. The fax phone numbers

for the organization where this application or proceeding is assigned are 703-872-9306

for all communications.

Any inquiry of a general nature or relating to the status of this application or

proceeding should be directed to the receptionist whose telephone number is (703) 306-

3431.

tld

02/2004

Minhloan Tran Primary Examiner

Page 7

Art Unit 2826